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| INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary) | | Application Number | 10/809,650 |
| | | Filing Date | 25 March 2004 |
| | | First Named Inventor | Michel Cote et al. |
| | | Group Art Unit | unknown 1752 |
| | | Examiner Name | unknown [signature] |
| Sheet | 1 | of | 3 |
| | | Attorney Docket Number | NMTI 1002-27 |

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| [initials] | C1 | SAKATA, MIWA, et al., "A Novel Radiation Sensitive Spin-on-glass Convertible into SiO ₂ and the Simple Fabrication Process Using It," 26 July 1993* (*ATI Bell Labs fax date), 3 pages. | |
| [initials] | C2 | PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages | |
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| [initials] | | RHYNS, P., et al., "Characterization of Quartz Etched PSM Masks for KrF Lithography at the 100 nm node," Proceedings of SPIE 4562 (March 2002), 486-495. | |
| [initials] | | SEWELL, HARRY, et al., "An Evaluation of the Dual Exposure Technique," (As early as 2002*), 11 pages *The date is based on references 8&9 of the article of 16 Feb 2001 and 27 Feb 2002, respectively. | |
| [initials] | | WANG, RUOPING, et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE 4754-105, 25 April 2002, 12 pages. | |
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| [initials] | | WONG, ALFRED K., "Polarization Effects in Mask Transmission," Proc. of SPIE 1674, 8 March 1992, 8 pages. | |
| [initials] | | ACKMANN, PAUL, et al., "Phase Shifting and Optical Proximity Corrections to improve CD control on Logic Devices in Manufacturing for sub 0.35 um I-Line," Proc. of SPIE 3051-07, March 1997, 8 pages. | |
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| JK | | SUGAWARA, MINORU, et al., "Defect printability study of attenuated phase-shifting masks for specifying inspection sensitivity," Proc. SPIE 2621-49, September 1995, 16 pages. | |
| JK | | SCHMIDT, REGINA, et al., "Impact of Coma on CD Control for Multiphase PSM Designs," Proc. SPIE 3334-02, February 1998, 11 pages. | |
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| JK | | MORIKAWA, YASUTAKA, et al., "100nm-Alt.PSM structure discussion for ArF lithography," Proc. SPIE 4409-22, April 2001, 15 pages. | |
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| AK | | SUZUKI, AKIYOSHI, et al., "Multilevel imaging system realizing k1=0.3 lithography," Proc. SPIE 3679-36, March 1999, 13 pages. | |
| AK | | VANDENBERGHE, G., et al., "(Sub-) 100nm gate patterning using 248nm alternating PSM," Mentor Graphics White Paper, May 2001, 9 pages. | |
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| AK | | FUKUDA, HIROSHI, et al., "Patterning of Random Interconnect Using Double Exposure of Strong-Type PSMs," Proc. SPIE 4346-695, September 2001, 8 pages. | |
| AK | | FERGUSON, RICHARD A., et al., "Pattern-Dependent Correction of Mask Topography Effects for Alternating Phase-Shifting Masks," Proc. SPIE 2440-349, May 1995, 12 pages. | |
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| AK | | MCCALLUM, MARTIN, et al., "Alternating PSM Mask Performance - A Study of Multiple Fabrication Technique Results," Proc. SPIE 4346-723, September 2001, 6 pages. | |

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